Docket No.: 020732-97.668 (7493) Appl. No. 10/792,038

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Docket No.: In re United States Patent Application of: 020732-97.668 (7493)**Applicants:** RATH, Melissa K., et al. Conf. No.: 4823 Art Unit: **Application No.:** 10/792,038 1752 Date Filed: March 3, 2004 **Examiner:** LE, Hoa Van Title: COMPOSITION AND PROCESS FOR **Customer No.:** 24239 POST-ETCH REMOVAL OF PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL DEPOSITED ON A **SUBSTRATE**

AMENDMENT RESPONDING TO FEBRUARY 24, 2009 OFFICE ACTION IN UNITED STATES PATENT APPLICATION NO. 10/792,038

Mail Stop Final Commissioner for Patents PO Box 1450 Alexandria, VA 22313-1450

Sir:

This responds to the February 24, 2009 Office Action in the above-identified application.

Please amend the claims, as set out in the following Section I (the Claims).

Remarks addressing the substance of the February 24, 2009 Office Action are set out in the **Section II** (**Remarks**) hereof.